

EV 26161597

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Priority Application Serial No. 09/026,042
Priority Filing Date February 19, 1998
Inventor Sujit Sharan et al.
Assignee Micron Technology, Inc. and Applied Materials, Inc.
Priority Group Art Unit 1763
Priority Examiner P. Hassanzadeh, Ph.D.
Attorney's Docket No. MI22-1902
TITLE: RF Powered Plasma Enhanced Chemical Vapor Deposition Reactor and
Methods of Effecting Plasma Enhanced Chemical Vapor Deposition

Assistant Commissioner for Patents
Washington, D. C. 20231
Attention: Official Draftsman


SUBSTITUTE DRAWING REQUEST

Please enter the enclosed substitute drawings in the above-referenced application in place of drawings originally filed. The content of the drawings are identical to those now on file in this application.

Acknowledgment of receipt of the formal drawings and their acceptance into the file is requested.

Respectfully submitted,

Date: Feb 19, 2002

By: 
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Enclosures: 4 Sheets of Formal Drawings, Figs. 1-6.

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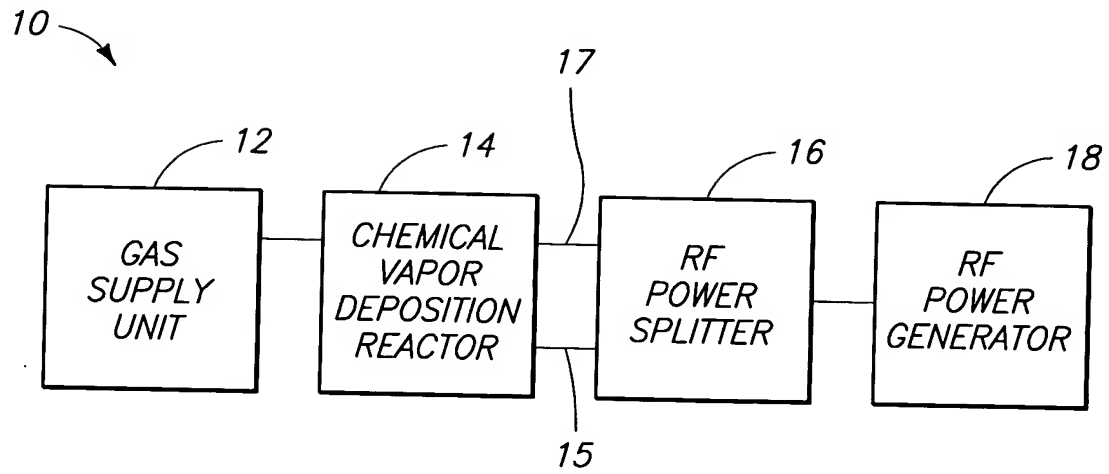


FIG. 1

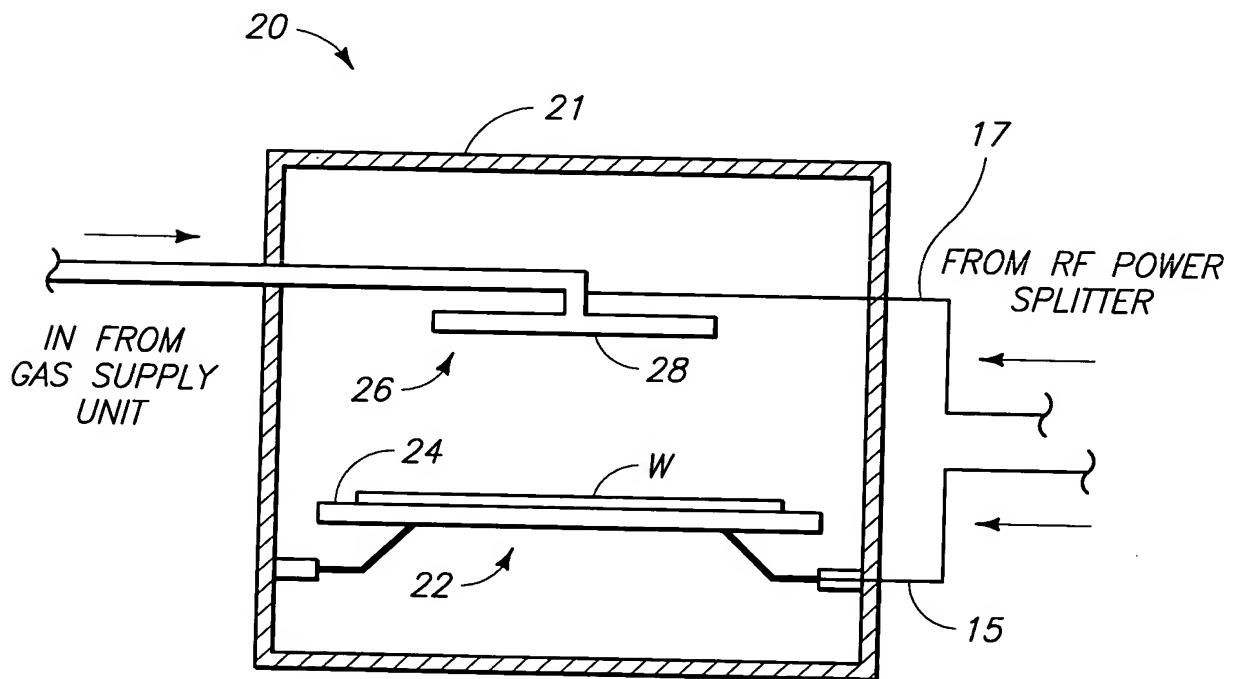


FIG. 2

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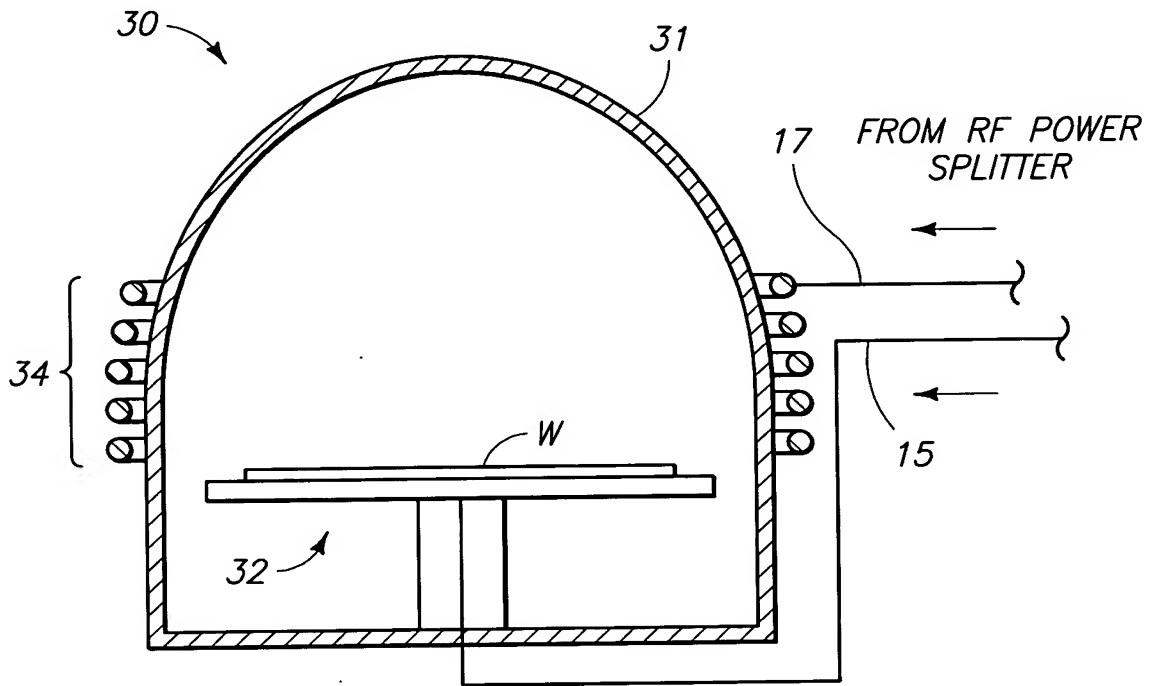


FIG. 2

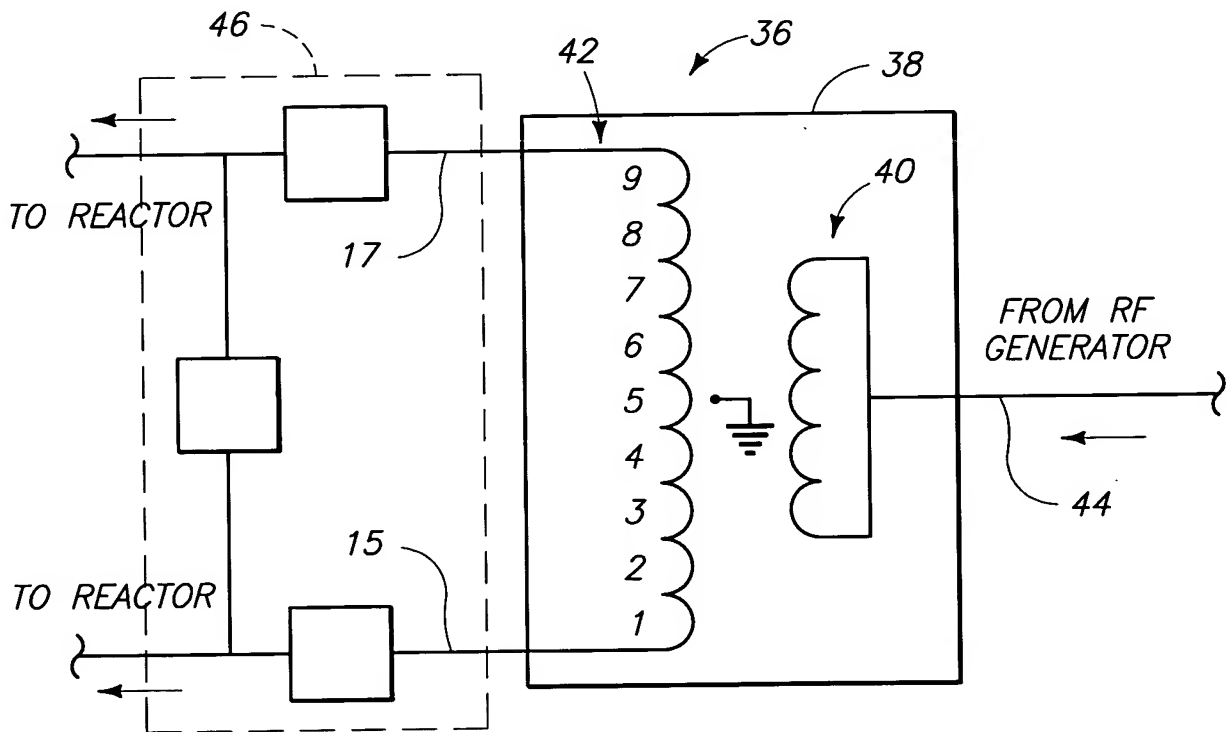


FIG. 3

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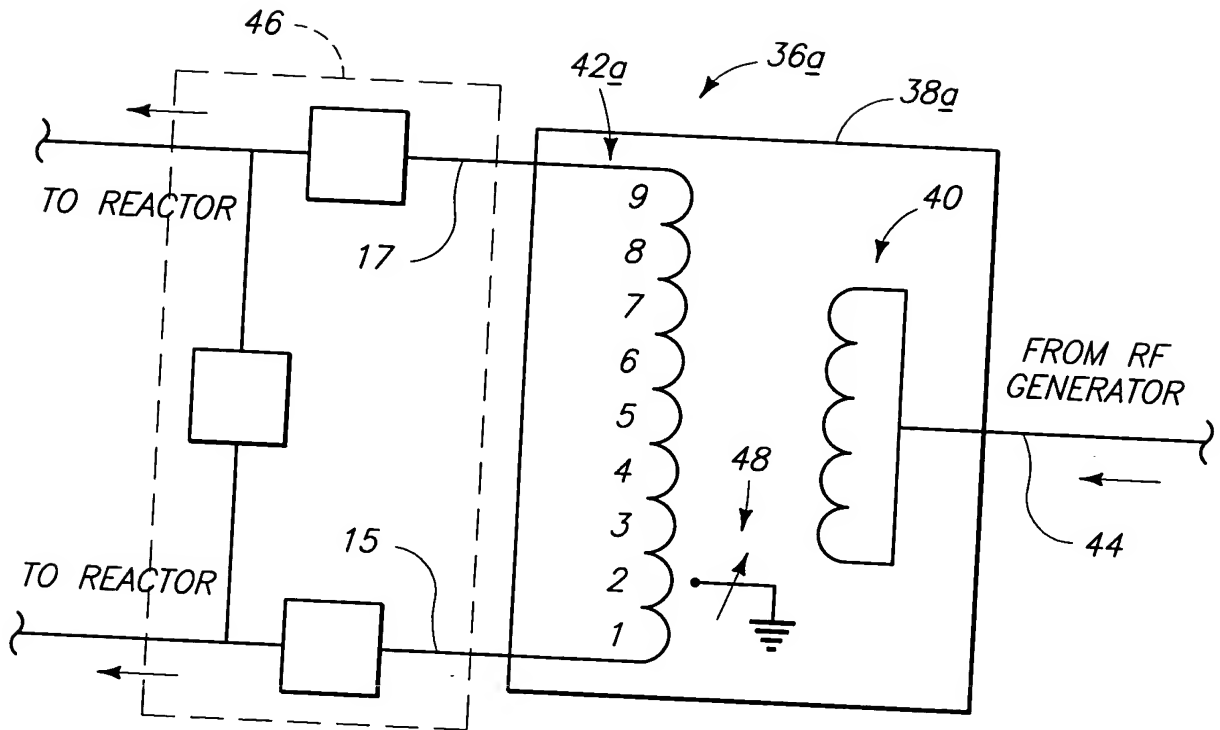


FIG. 5

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